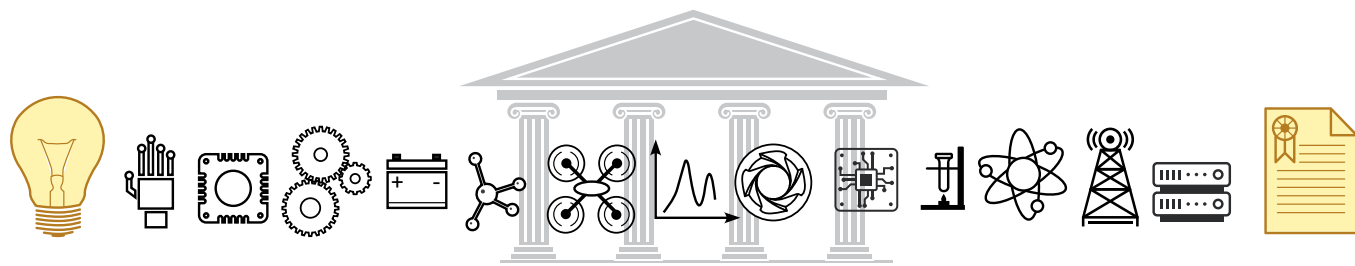


# Looking at Patent Law: Opportunity Prospecting by Analysis of Analogous Patent Art

by E. Jennings Taylor and Maria Inman



In this article we discuss the use of patent citation analysis to identify additional technology applications and potential collaborators or licensees for the patented technology. U.S. law stipulates<sup>1</sup> that:

*“[Patents] shall have the attributes of personal property.”*

As we noted in a previous article<sup>2</sup> in *Interface*, the analogy between real property and intellectual property (patents) can provide helpful perspective. Of particular relevance to patent citation analysis is the analogy between the deed of real property and the claims of a patent. The deed defines the boundaries of ownership by the owner of the real property. The patent claims define the boundaries of ownership by the assignee of the patent. Recall, inventors are generally obligated to assign patent rights to their employer.<sup>3</sup> In the case of real property, modern surveying methods lead to precise determination of the boundaries of the real property described in the deed. In the case of a patent, the courts have recognized that language can be imprecise:<sup>4</sup>

*“The nature of language makes it impossible to capture the essence of a thing in a patent application [claim].”*

Consequently, the intellectual property “boundaries” defined by the claims are often referred to as the “metes and bounds” of the patent. The “metes and bounds” description is derived from an early system of defining the boundaries of real property, where the boundaries are described by the local geography of the parcel of land and are therefore somewhat imprecise.

Related to our discussion of opportunity prospecting, when a prospective buyer initiates the purchase of a parcel of land, a search is conducted by a title company to ensure there are no previous owners or legal encumbrances on the real property. During this search, the title company identifies previous owners, current owners, and neighboring properties.

Analogously, when an inventor files a patent application, an examination of the prior art is conducted by the U.S. Patent & Trademark Office (USPTO) to ensure there are no previous owners

of all or part of the claimed invention upon which the pending patent application would “trespass.” If prior art is identified that impacts the patentability of a patent application, then the inventor may limit the claims of her/his patent application in order to overcome said prior art. In addition, during the prior art search, the patent examiner identifies background or “neighboring” prior art patents, published patent applications and other publications. Consequently, inventors have the opportunity to become aware of a rich landscape of prior art during examination of their patent applications.

Similarly, after a patent application is published and/or subsequently issues, it becomes part of the prior art landscape. Consequently, once a Faraday patent issues, we find it valuable to review the prior art landscape of “backward” citations cited during the examination of the patent application. Additionally, we continue to monitor U.S. Patent & Trademark Office actions to identify “forward” citations where Faraday patents are referenced as prior art against subsequent patent applications. These forward or “referenced by” citations provide the basis for opportunity prospecting by analysis of this analogous prior art. Herein we provide an actual case study illustrating the use of patent citation analysis to identify additional technology applications and potential collaborators or licensees for one of Faraday’s patented technologies. To begin the case study, we provide a brief background of Faraday Technology Inc. as perspective.

Our perspective is based on over 25 years of experience at Faraday Technology Inc., a research, development, and engineering company, that was founded in 1991 to conceive, develop, and commercialize novel electrochemical technologies based on pulse current/pulse reverse current (PC/PRC) electrolytic principles. Excellent reviews on PC/PRC plating are available in the seminal work edited by

*(continued on next page)*

Puipe<sup>5</sup> and more recently updated.<sup>6</sup> Our unique approach to PC/PRC plating AND surface finishing are summarized as well<sup>7,8</sup> and illustrated in the company vision:

*“To develop robust and environmentally friendly electrochemical deposition and surface finishing processes based on simple electrolytes enabled by pulse/pulse reverse electric fields.”*

The company’s mission is to conceive and commercialize electrochemical processes based on the PC/PRC technology platform. To support these activities, funding is obtained through the U.S. Small Business Innovative Research (SBIR) and Small Business Technology Transfer (STTR) programs. These programs consist of a Phase I feasibility demonstration activity followed by a Phase II technology development and validation activity. Once the Phase II development activity has been completed, commercialization of the technology for private sector use or transition of the technology for government use comes from private sector or non-SBIR government funding, respectively. Critically, while the SBIR/STTR programs represent a highly competitive source of technology demonstration and validation funding, these programs allow the small business to retain assignment of the inventions “conceived or first actually reduced to practice” with said funds.<sup>9</sup>

We first demonstrated the effectiveness of PC/PRC surface finishing of automotive planetary gears by replacing a DC electrochemical deburring process based on ethylene glycol with a PC process using a low concentration aqueous salt solution.<sup>10</sup> Building on the deburring results, we obtained Phase I and II SBIR funding from the National Science Foundation to demonstrate the ability to use PRC to electropolish nickel alloy coupons in low concentration aqueous salt solution.<sup>11</sup> This work provided the basis for two patents assigned to Faraday.

Subsequently, we were approached by an engineer from a manufacturer of stainless steel valves for the semiconductor industry. The manufacturer employed conventional DC electropolishing as the final step for surface finishing of their stainless steel valves, fittings and tubular products. The conventional electropolishing process was based on the well-established viscous salt film paradigm<sup>12</sup> and used a chilled electrolyte solution consisting of concentrated sulfuric/phosphoric acid as well as proprietary additives that may have included fluoride species.

Under a stage-gated research-for-hire activity, we demonstrated the ability to electropolish their stainless steel coupons using PRC in conjunction with a low concentration aqueous salt electrolyte. We subsequently demonstrated and validated the PRC electropolishing process on actual stainless steel products using an  $\alpha$ -scale manufacturing apparatus in Faraday’s prototyping facility. For competitive reasons, the manufacturing company wanted to retain exclusive rights to the subject technology and we negotiated a “field-of-use” license consistent with Faraday’s business model.<sup>13</sup> The field-of-use license was defined as follows:

1. Market – semiconductor
2. Product – valves and fittings
3. Material – stainless steel

The license was based on two patents (Fig. 1) covering the subject PRC electropolishing technology.<sup>14,15</sup>

As noted above, we continuously monitor our issued patents to review backward prior art citations and identify forward prior art citations. Specifically, we define them as follows:

1. Backward prior art citations: Prior art cited by Faraday inventors and/or the USPTO examiner during the prosecution of the Faraday patent application,
2. Forward prior art citations: Citations of the Faraday patent as prior art by the inventors and/or the USPTO examiner during the prosecution of subsequent patent applications.

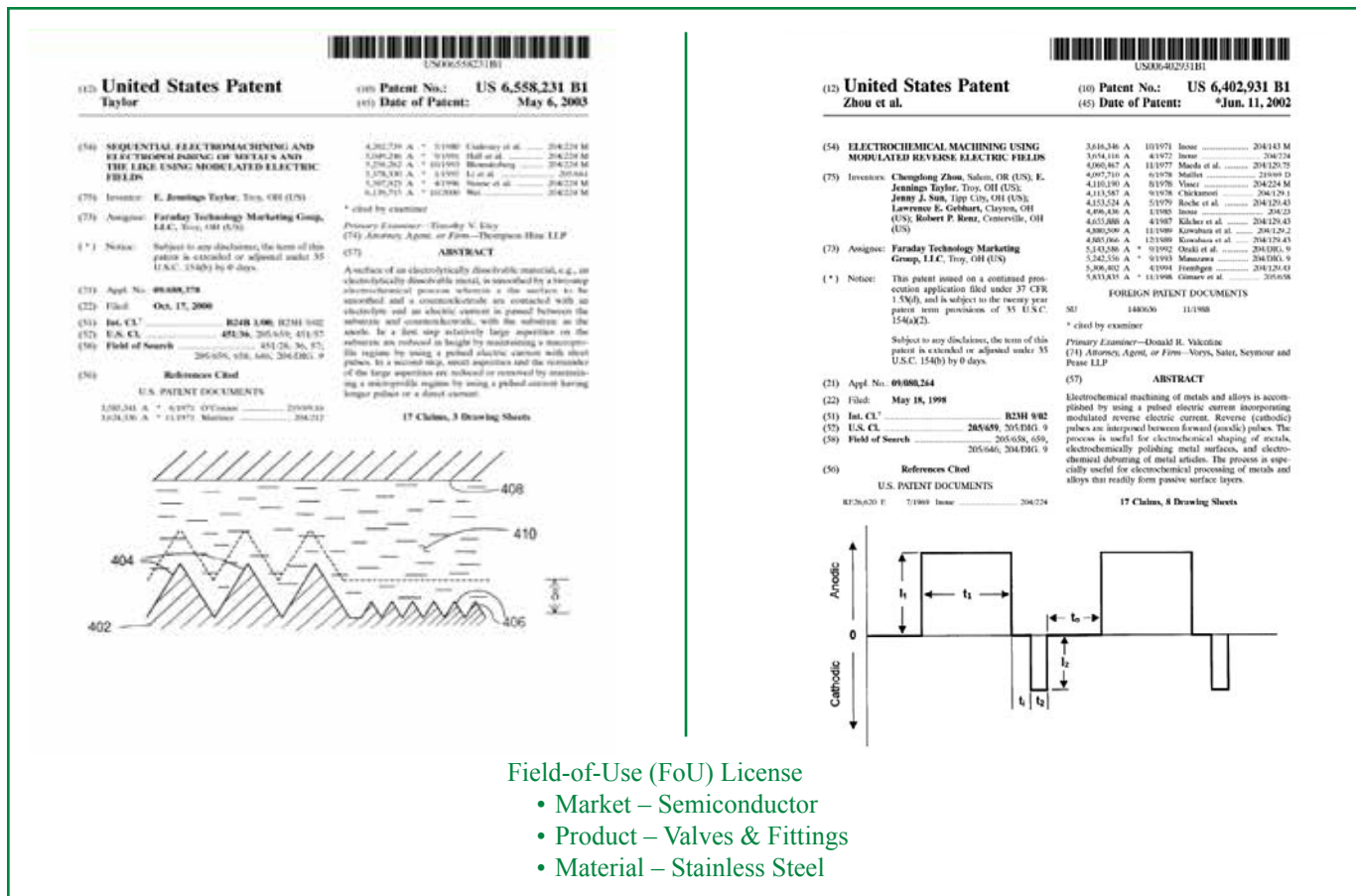


Fig. 1. Faraday patent nos. 6,402,931 and 6,558,231 licensed to valve manufacturer.

**Sequential electromachining and electropolishing of metals and the like using modulated electric fields**  
US 6558231 B1

**ABSTRACT**

A surface of an electrochemically dissolvable material, e.g., an electrochemically dissolvable metal, is smoothed by a two-step electrochemical process wherein a surface to be smoothed and a counterelectrode are contacted with an electrolyte and an electric current is passed between the substrate and counterelectrode, with the substrate as the anode. In a first step relatively large asperities on the substrate are reduced in height by maintaining a macroprofile regime by using a pulsed electric current with short pulses. In a second step, small asperities and the remainder of the large asperities are reduced or removed by maintaining a microprofile regime by using a pulsed current having longer pulses or a direct current.

Publication number: US6558231 B1  
 Publication type: Grant  
 Application number: US 09/688,378  
 Publication date: May 6, 2003  
 Filing date: Oct 17, 2000  
 Priority date: Oct 17, 2000  
 Fee status: Paid  
 Also published as: WO2003045262A1  
 Inventors: E. Jennings Taylor  
 Original Assignee: Faraday Technology Marketing Group, LLC  
 Export Citation: EBTx, Esp@nol, RefMan  
 Patent Citations (8), Referenced by (29), Classifications (15), Legal Events (6)  
 External Links: USPTO, USPTO Assignment, Espacenet

Backward Citations (8)      Forward Citations (29)

Fig. 2. Google patent search results for Faraday patent no. 6,558,231.

These citations are easily tracked using the USPTO website<sup>16</sup> or “Google patents.”<sup>17</sup> In Fig. 2, we illustrate the search results for U.S. patent no. 6,558,231 (referred to below as the ‘231 patent) using Google Patents accessed on September 12, 2017. From the first page, we see that there were eight (8) background or prior art “patent citations” during the prosecution of the ‘231 patent. This number does not change as a function of the date the Google Patents database is accessed. In addition, we see that there are twenty-nine (29) forward

review of the claims, we noted that many of the dependent claims were directed towards strong acid electrolytes with additions of chelating agents. This approach is in contrast to Faraday’s approach to development of PC/PRC electrochemical processes based on simple aqueous electrolytes.

To summarize, based on this straightforward and simple preliminary analysis, we identified a potential new application, of which we were not previously aware, for Faraday’s PC/PRC process

development activities. A more detailed understanding of the prior art citation of Faraday’s ‘231 patent application may be obtained by reviewing the file history of the prosecution of the ‘411 patent at the USPTO Patent Application Information Retrieval (PAIR) website portal.<sup>19</sup>

In Fig. 5, we illustrate the various documents within the “Image File Wrapper” for the ‘411 patent. These documents represent the correspondences between the USPTO examiner and the patent applicant during the prosecution of the subject patent application. These correspondences include the examiner’s prior art search, the examiner non-final and final rejection office actions, the applicant’s responses to non-final/final rejections, applicant’s amendments to claims, issue notification and so forth. Our review of the prosecution history of the ‘411 patent application indicates that Faraday’s ‘231 patent was used to support an “obviousness” (35 USC §103) rejection of the claims directed towards pulse reverse electropolishing.<sup>18</sup> The ‘411 patent applicant modified their claims to include limitations to the pulse reverse electropolishing method,

REFERENCED BY

Citing Patent	Filing date	Publication date	Applicant	Title
<a href="#">US6750148</a>	Feb 14, 2003	Jun 15, 2004	Faraday Technology Marketing Group, LLC	Method for electrochemical metalization and planarization of semiconductor substrates having features of different sizes
<a href="#">US6646227 *</a>	Feb 28, 2002	Jan 25, 2005	Sony Corporation	Electro-chemical machining apparatus
<a href="#">US7022216</a>	Jun 11, 2003	Apr 4, 2006	Faraday Technology Marketing Group, LLC	Electrolytic etching of metal layers
<a href="#">US7153411 *</a>	Dec 30, 2003	Dec 26, 2006	Boston Scientific Scimed, Inc.	Method for cleaning and polishing metallic alloys and articles cleaned or polished thereby
<a href="#">US7553401</a>	Mar 19, 2004	Jun 30, 2009	Faraday Technology, Inc.	Electropolishing cell with hydrodynamics facilitating more uniform deposition across a workpiece during plating
		Jul 24, 2011	Faraday Technology, Inc.	Method of operating an electroplating cell with hydrodynamics facilitating more uniform deposition on a workpiece with through holes
<a href="#">US7998334 *</a>	Apr 22, 2003	Aug 16, 2011	Koninklijke Philips Electronics, N.V.	Method, an apparatus, a control system and a computer program to perform an automatic removal of cathode depositions during a bipolar electrochemical machining
<a href="#">US8123927 *</a>	Sep 23, 2003	Feb 28, 2012	Rockstar Bidco, LP	Reduced circuit trace roughness for improved signal performance
<a href="#">US8226804</a>	Apr 14, 2011	Jul 24, 2012	The United States Of America As Represented By The Secretary Of The Air Force	Electropolishing cell with hydrodynamics facilitating more uniform deposition on a workpiece with through holes during plating
<a href="#">US8329006</a>	Apr 28, 2009	Dec 11, 2012	Faraday Technology, Inc.	Electropolishing cell with hydrodynamics facilitating more uniform deposition across a workpiece during plating
<a href="#">US8764515 *</a>	May 14, 2012	Jul 1, 2014	United Technologies Corporation	Component machining method and assembly
<a href="#">US9006147</a>	Jul 11, 2012	Apr 14, 2015	Faraday Technology, Inc.	Electrochemical system and method for electropolishing superconductive radio frequency cavities
<a href="#">US2002016068 *</a>	Feb 28, 2002	Oct 31, 2002	Shuazo Sato	Electro-chemical machining apparatus
<a href="#">US2004004006 *</a>	Jun 11, 2003	Jan 8, 2004	Taylor E. Jennings	Electrolytic etching of metal layers
<a href="#">US20040011696 *</a>	Jan 11, 2003	Jan 22, 2004	Taylor E. Jennings	Electrolytic etching of metal layers
<a href="#">US20050082165 *</a>	Nov 8, 2004	Apr 21, 2005	Shuazo Sato	Electro-chemical machining apparatus
<a href="#">US20050145586 *</a>	Dec 29, 2003	Jul 7, 2006	Taylor E. J.	Electrochemical etching of circuitry for high density interconnect electronic modules
<a href="#">US20050145688 *</a>	Dec 30, 2003	Jul 7, 2006	Scimed Life Systems, Inc.	Method for cleaning and polishing steel-titanium alloys

Boston Scientific

Fig. 3. Forward citations for Faraday patent no. 6,558,231.

or “referenced by” citations as of the date the Google Patent database was accessed. Clearly, these forward citations can change with time as subsequent patent applications issue. For our trivia readers, U.S. patents always issue on a Tuesday.

By selecting the “Referenced by” hyperlink, we are taken to the Google patent page with the 29 forward prior art patent citations shown in part in Fig. 3. This page provides the citing patent or patent application number, filing date, publication date, assignee, and title of the patent/patent application. For the prior art highlighted with an asterisk (\*), the ‘231 patent was cited as prior art by the USPTO examiner during prosecution of the citing patent. For the prior art without a highlight, the ‘231 patent was cited as prior art by the applicant during prosecution of the citing patent.

Upon scanning the list of forward citation prior art, we observe a number of Faraday patents/patent applications and patents/patent applications generally related to electrochemical machining or electrochemical polishing. Of particular interest for this case study is patent no. 7,153,411 (referred to below as the ‘411 patent) assigned to Boston Scientific Scimed, Inc. The highlighted “\*” associated with the ‘411 patent indicates that the USPTO examiner cited the ‘231

which then allowed the patent to issue. As discussed earlier, there still could be “freedom to operate” issues associated with the ‘411 patent.<sup>2</sup>

With this analysis of analogous patent art, we identified a new opportunity for our platform PC/PRC technology directed towards electropolishing of medical stents in simple aqueous electrolytes enabled by our pulse reverse current approach. We successfully pursued funding from the National Institutes of Health (NIH) SBIR program and were awarded Phase I and Phase II projects. With this funding, we demonstrated the feasibility of electropolishing medical stent materials (nickel-titanium) in simple aqueous electrolytes.<sup>20</sup> Subsequently, we worked with a supplier of nickel-titanium wire for stent applications to demonstrate and validate the pulse reverse electropolishing process in an  $\alpha$ -scale reel-to-reel electropolishing apparatus consisting of 300 and 5,000 foot wire spools.<sup>21</sup> These activities led to a license of the same two patents licensed to the semiconductor valve manufacturer but for a different “field-of-use” defined as follows:

1. Market – medical
2. Product – wire based stents and shape sets
3. Material – nickel-titanium alloys

(continued on next page)

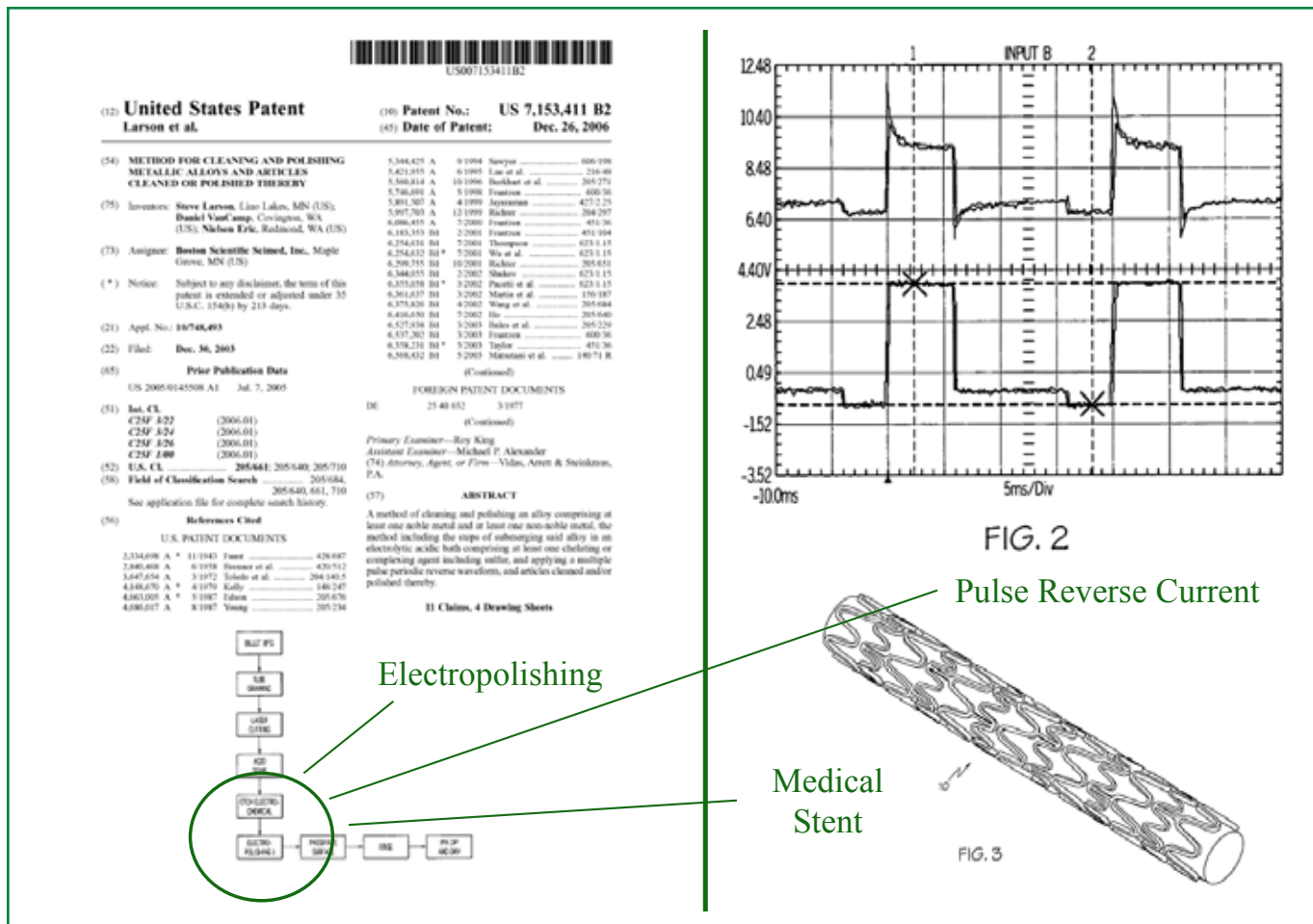


Fig. 4. Boston Scientific patent no. 7,153,411 citing Faraday patent no. 6,558,231.

In summary, we presented a case study for opportunity prospecting by analysis of analogous patent art (Fig. 6). The approach uses forward or “referenced” by patent citation analysis to identify examiner or applicant prior art citations of the patent of interest during the prosecution of subsequent patent applications. The prior art citation analysis was illustrated using the Google patent search but is also easily conducted using the USPTO patent Boolean search function. While the case study was based on the experience at Faraday Technology Inc., an electrochemical research, development and engineering company with an electrochemical platform technology, we believe the approach would be valuable for other businesses, universities and federal laboratories. More specifically, we suggest that electrochemical scientists, engineers and technologists consider the patent literature in addition to their review of the technical literature.

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### About the Authors



**E. JENNINGS TAYLOR** is the founder of Faraday Technology, Inc., a small business focused on developing innovative electrochemical processes and technologies based on pulse and pulse reverse electrolytic principles. Jennings leads Faraday’s patent and commercialization strategy and has negotiated numerous via field of use licenses as well as patent sales. In addition to technical publications and presentations,

Jennings is an inventor on forty patents. Jennings is admitted to practice before the United States Patent & Trademark Office (USPTO) in patent cases as a patent agent (Registration No. 53,676) and is a

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<http://orcid.org/0000-0003-2560-8410>

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- E. Jennings Taylor and Maria Inman “Looking at Patent Law: Why Is the Word ‘Right’ Mentioned Only Once in the Constitution of the United States?” *Electrochem. Soc. Interface*, **26**(2), 45 (2017).

Mail Room Date	Document Code	Document Description	PROSECUTION
12-05-2000	ISSUE.NTF	Issue Notification	1
11-10-2000	1449	List of References cited by applicant and examiner	PRIOR ART
11-03-2000	IFEE	Issue Fee Payment (PTO 850)	PROSECUTION
09-25-2000	NOA	Notice of Allowance and Fees Due (PTOL 65)	PROSECUTION
09-25-2000	NOA	Notice of Allowance and Fees Due (PTOL 65)	PROSECUTION
09-25-2000	IFW	Issue Information including classification, examiner, name, claim, renumbering, etc.	PROSECUTION
09-25-2000	ANE.1	Amendment After Final or under 37CFR 1.312, initiated by the examiner.	PROSECUTION
09-25-2000	RIW	Bibliographic Data Sheet	PROSECUTION
09-25-2000	SRFW	Search information including classification, databases and other search related notes	PROSECUTION
09-10-2000	SPNT	Examiner's search strategy and results	PROSECUTION
09-08-2000	ALNE	Response After Final Action	PROSECUTION
09-08-2000	CLM	Claims	PROSECUTION
09-08-2000	SPEC	Specification	PROSECUTION
09-08-2000	REM	Applcmt Arguments/Remarks Made in an Amendment	PROSECUTION
09-08-2000	WFEE	Fee Worksheet (2806)	PROSECUTION
07-24-2000	CTAV	Advisory Action (PTOL 302)	PROSECUTION
07-24-2000	ANE.1	Amendment After Final or under 37CFR 1.312, initiated by the examiner.	PROSECUTION
07-10-2000	ALNE	Response After Final Action	PROSECUTION
07-10-2000	CLM	Claims	PROSECUTION
07-15-2000	REM	Applcmt Arguments/Remarks Made in an Amendment	PROSECUTION
07-10-2000	WFEE	Fee Worksheet (2806)	PROSECUTION
07-10-2000	PWCLM	Process of Claims	PROSECUTION
09-07-2000	CTFR	Final Rejection	PROSECUTION
09-07-2000	892	List of references cited by examiner	PROSECUTION
09-07-2000	FOR	Foreign Reference	PROSECUTION
09-07-2000	SRFW	Search information including classification, databases and other search related notes	PROSECUTION
09-01-2000	SPNT	Examiner's search strategy and results	PROSECUTION
09-01-2000	A...	Amendment/Req. Reconsideration After Non-Final Rejection	PROSECUTION
09-01-2000	CLM	Claims	PROSECUTION
09-01-2000	REM	Applcmt Arguments/Remarks Made in an Amendment	PROSECUTION
09-01-2000	WFEE	Fee Worksheet (2806)	PROSECUTION
03-01-2000	CTNF	Non Final Rejection	PROSECUTION
03-01-2000	892	List of references cited by examiner	PRIOR ART
03-01-2000	FOR	Foreign Reference	PRIOR ART
03-01-2000	FOR	Foreign Reference	PRIOR ART
03-01-2000	FOR	Foreign Reference	PRIOR ART
03-01-2000	SRFW	Search information including classification,	PROSECUTION

Fig. 5. Image file wrapper for Boston Scientific patent no. 7,153,411.

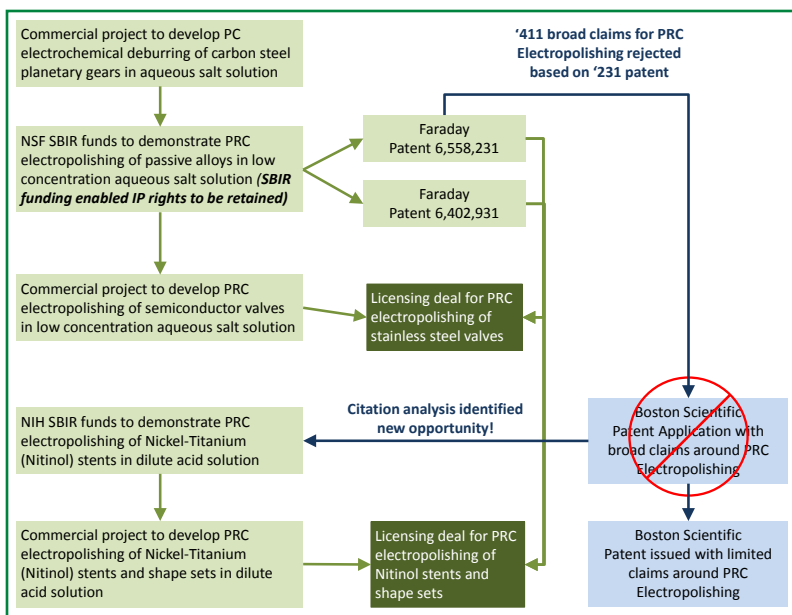


Fig. 6. Case study of opportunity prospecting.

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